

# Notice of Allowability

Application No.

10/781,870

Examiner

John S. Chu

Applicant(s)

LIAO ET AL.

Art Unit

1752

## -- The MAILING DATE of this communication appears on the cover sheet with the correspondence address--

All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. **THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS.** This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.

1. ☒ This communication is responsive to 1/25/06.
2. ☒ The allowed claim(s) is/are 1-6.
3. ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
  - a) ☒ All b) ☐ Some\* c) ☐ None of the:
    1. ☒ Certified copies of the priority documents have been received.
    2. ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.
    3. ☐ Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).

\* Certified copies not received: \_\_\_\_\_.

Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.  
**THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.**

4. ☐ A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.
  5. ☐ CORRECTED DRAWINGS ( as "replacement sheets") must be submitted.
    - (a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review ( PTO-948) attached
      - 1) ☐ hereto or 2) ☐ to Paper No./Mail Date \_\_\_\_\_.
    - (b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date \_\_\_\_\_.
- Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).
6. ☐ DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.

### Attachment(s)

1. ☐ Notice of References Cited (PTO-892)
2. ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/08), Paper No./Mail Date \_\_\_\_\_
4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material
5. ☐ Notice of Informal Patent Application (PTO-152)
6. ☐ Interview Summary (PTO-413), Paper No./Mail Date \_\_\_\_\_
7. ☐ Examiner's Amendment/Comment
8. ☒ Examiner's Statement of Reasons for Allowance
9. ☒ Other Drawings are accepted.

### **REASONS FOR ALLOWANCE**

1. The following is an examiner's statement of reasons for allowance: The claimed invention is drawn to the following:

**Claim 1. (Previously Presented) A method for high aspect ratio pattern transfer of positive photoresist application comprising the steps of:**

**(1) obtaining a moldboard being pervious to light and having a protruding-and-recessing figure and forming a masking layer by way of sputtering deposition of a masking material on said moldboard;**

**(2) after solidifying said masking layer, grinding the masking layer on the protruding part of said figure of said moldboard making said protruding part pervious to light;**

**(3) obtaining a substrate applied with positive photoresist and then urging the mold at a molding pressure into the film creating a thickness contrast pattern in the film, wherein the molding pressure is sufficiently high to transfer the features to the film and the molding pressure causes a local deformation in the mold which is less than the mold pattern lateral dimension with said substrate that has said protruding-and-recessing figure for further processing Step and Flash;**

**(4) after finishing said Step and Flash process, removing said moldboard from said substrate; and**

**(5) with a developer, washing exposed portions of the thin film covered with said positive photoresist on said substrate to show the unexposed portion whereby produces high aspect ratio pattern.**

None of the prior art references cited of record disclose or render obvious the claimed invention. As stated in the previous Office action, none of the prior art references of record disclose the recited method claims the step of grinding the masking layer at the protruding parts to form portions that are pervious to light. The moldboard is then pressed into a positive photoresist film and step and flash processed and subsequently developed to wash exposed portions and thus giving the high aspect ration patterns. Prior art references in the imprint processing art lack the mask formation as recited wherein the sputtered mask is grinded to form regions that are pervious to light wherein the imprinted photoresist is step and flash processed and finally developed.

Applicant's amendment to claim 4 overcomes the rejection outstanding under 35 U.S.C. 112, second paragraph as given in the Final rejection mailed November 2, 2005.

For the reasons stated above, claims 1-6 are seen as allowable and passed to issue.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

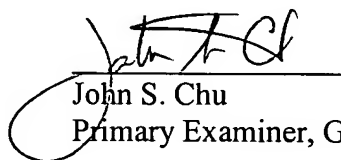
2. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Chu whose telephone number is (571) 272-1329. The examiner can normally be reached on Monday - Friday from 9:30 am to 6:00 pm.

If attempts to reach the Examiner by telephone are unsuccessful, the Examiner's supervisor, Cynthia Kelly, can be reached on (571) 272-1526

The fax phone number for the USPTO is (571) 273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PMR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).



John S. Chu  
Primary Examiner, Group 1700

J.Chu  
February 10, 2006